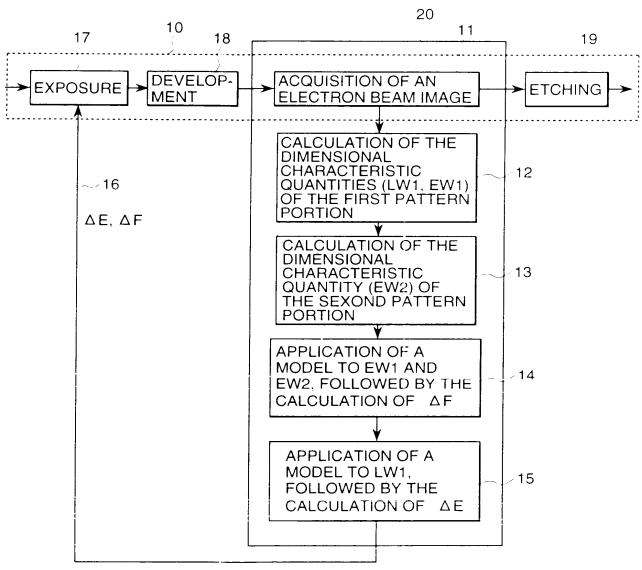
FIG. 1



LW: LINE WIDTH EW: EDGE WIDTH

FIG. 2

201 ELECTRON GUN 200 ELECTRONIC CONDENSING LENS **OPTICAL SYSTEM** 203 202 PRIMARY ELECTRON BEAM 207 SECONDARY ELECTRON DETECTOR ExB 300 IMAGE PROCESSING SECTION 204 DEFLECTÓR 208 205 < A/D **OBJECTIVE LENS** CPU - 304 CONVERTER 206 IMAGE **MEMORY** 100 WAFER 303 302 101 STAGE 301

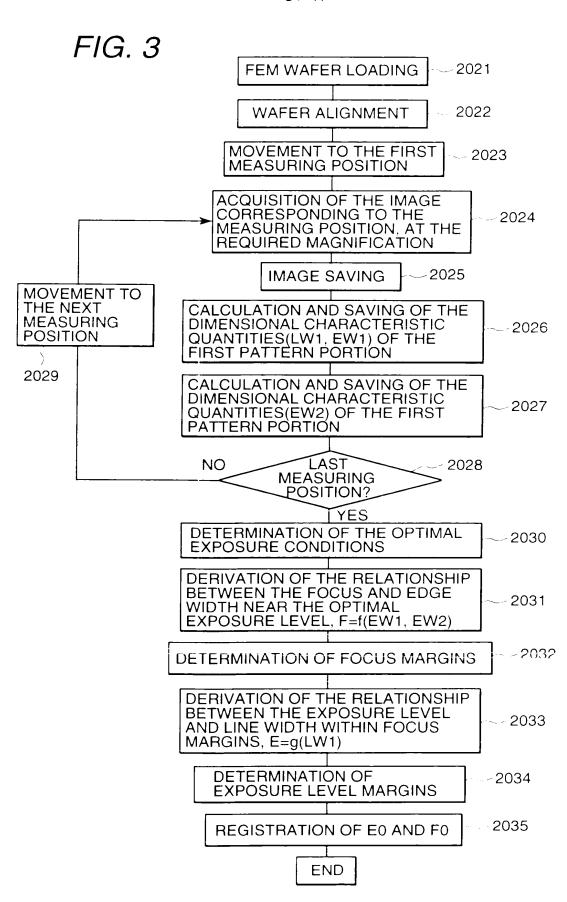
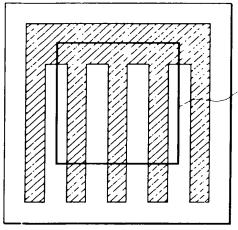


FIG. 4(a)



30 IMAGE ACQUISITION SECTION

WHITE: TRANSMITTING

PORTION

BLACK: SHIELDING

PORTION

FIG. 4(b)

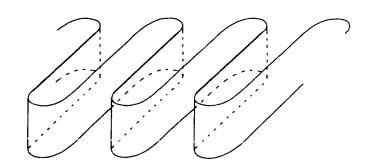


FIG. 4(c)

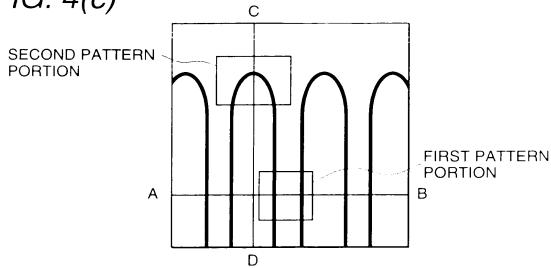


FIG. 5(a)

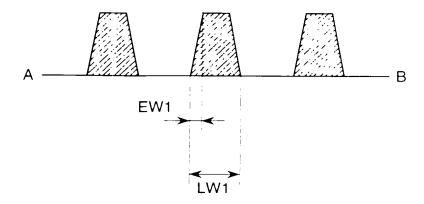


FIG. 5(b)

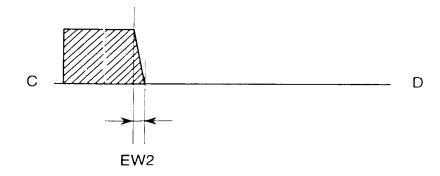


FIG. 5(c)

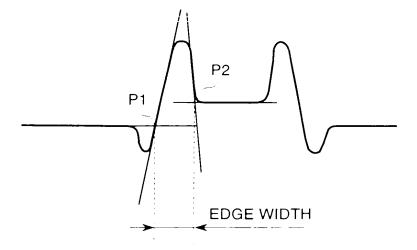


FIG. 6(a)

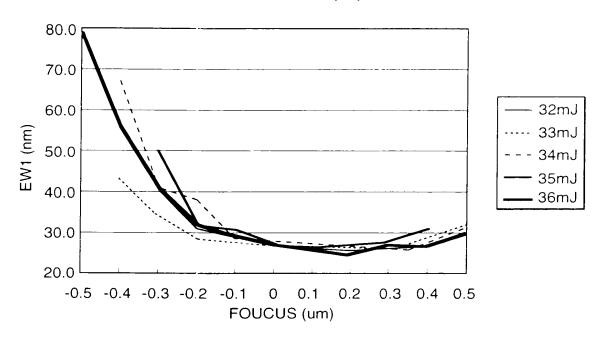


FIG. 6(b)

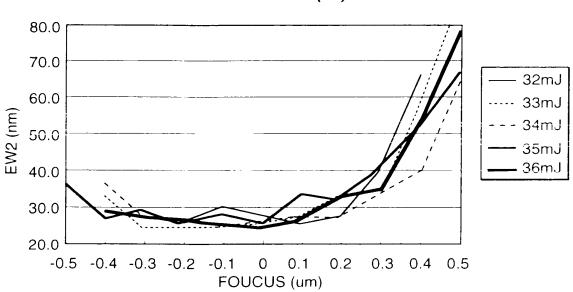


FIG. 17(a)

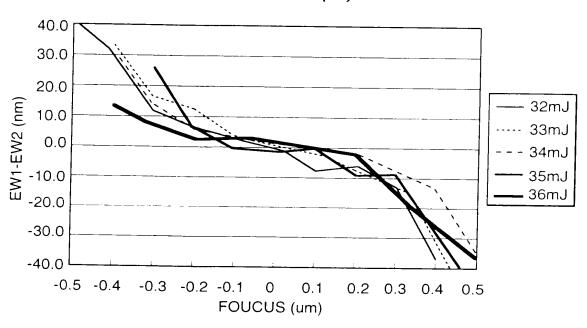


FIG. 17(b)

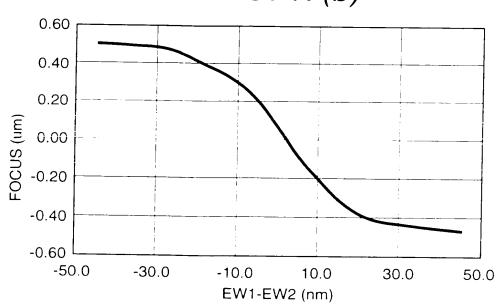


FIG. 8

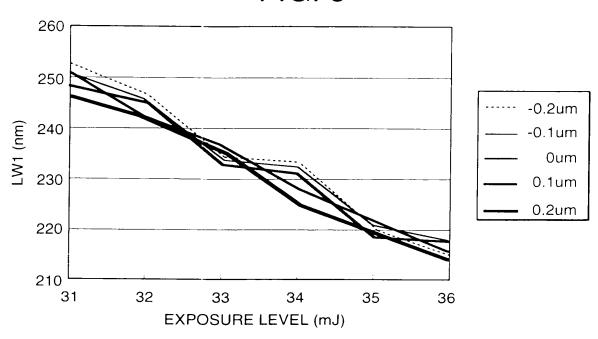


FIG. 11

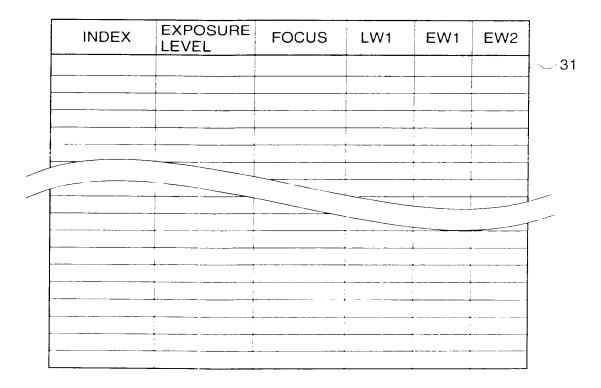


FIG. 9(a)

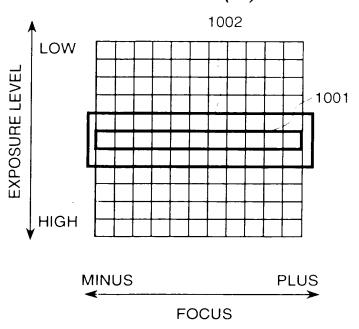


FIG. 9(b)

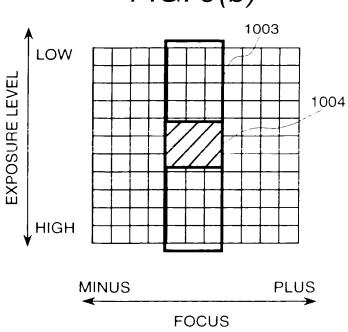


FIG. 10

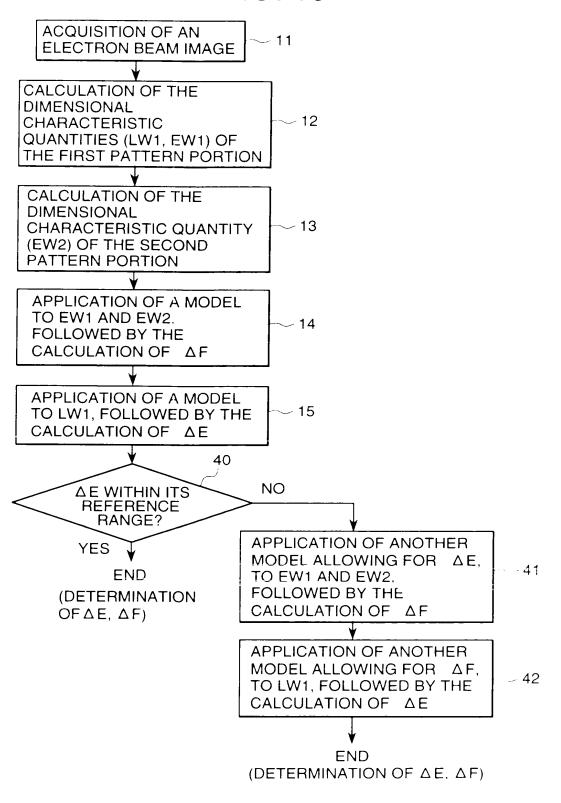


FIG. 12(a)

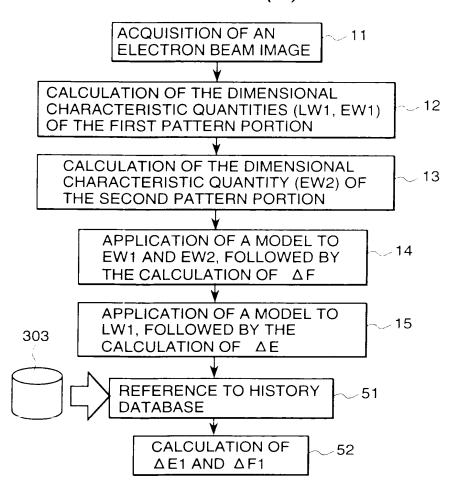


FIG. 12(b)

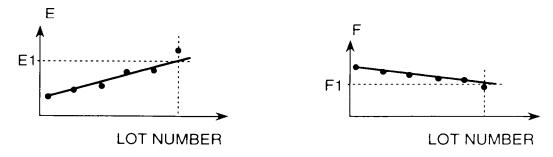
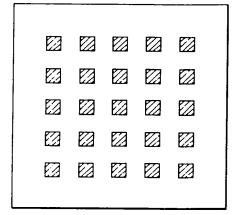


FIG. 13(a)

WHITE: TRANSMITTING PORTION BLACK: SHIELDING PORTION



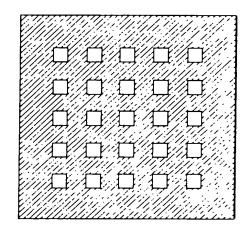


FIG. 13(b)

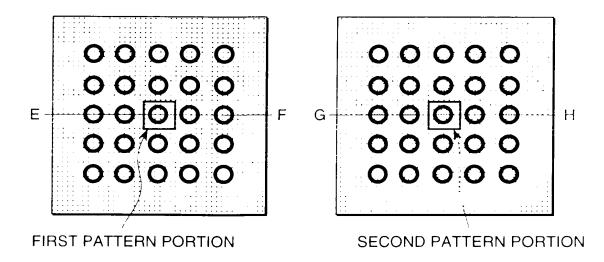


FIG. 14

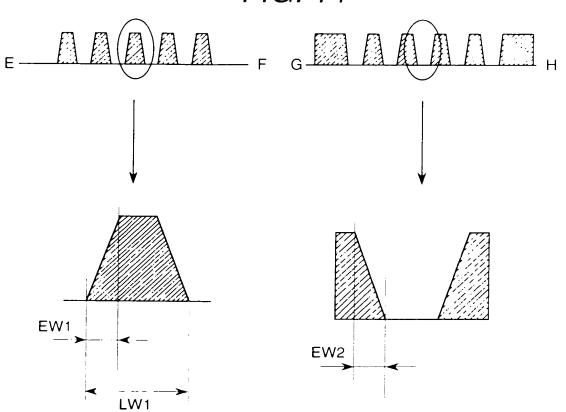


FIG. 15(a)

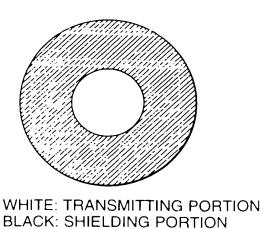


FIG. 15(b)

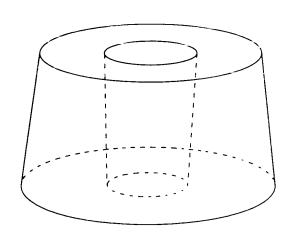


FIG. 16(a)

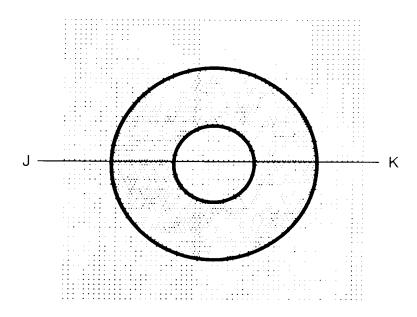


FIG. 16(b)

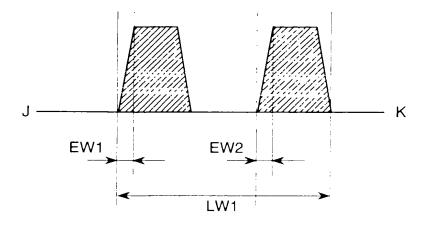
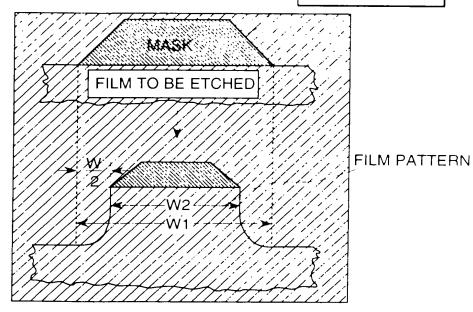


FIG. 17

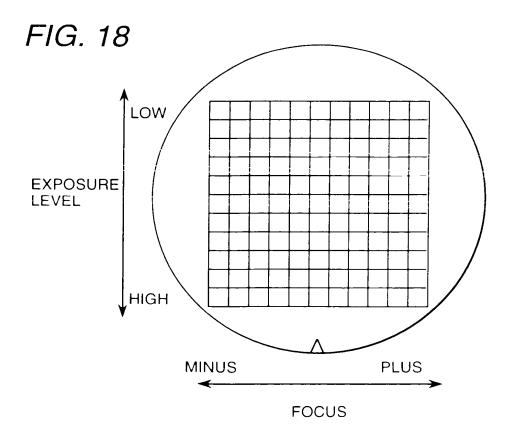
RESIST PATTERN



W1: WIDTH OF THE RESIST PATTERN BOTTOM

heta : ANGLE OF INCLINATION OF THE RESIST PATTERN

W2: WIDTH OF THE FILM PATTERN



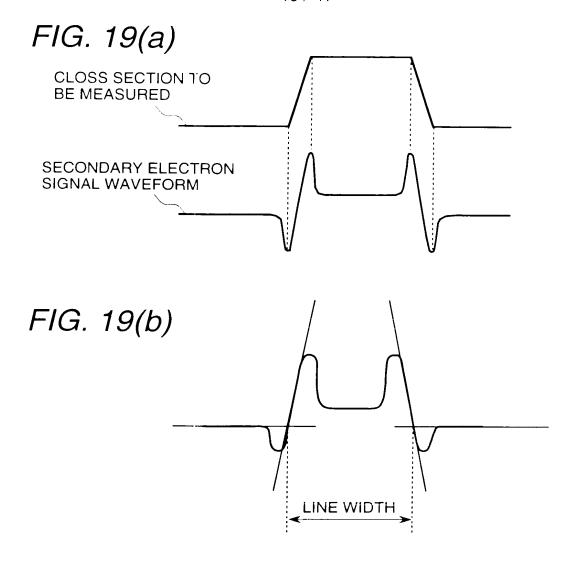


FIG. 21

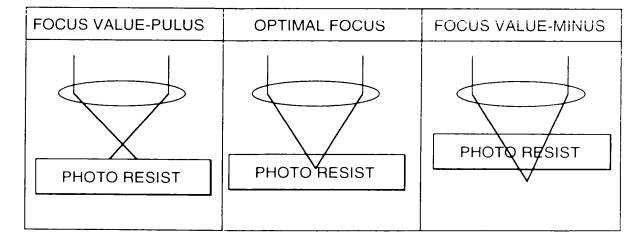


FIG. 20(a)

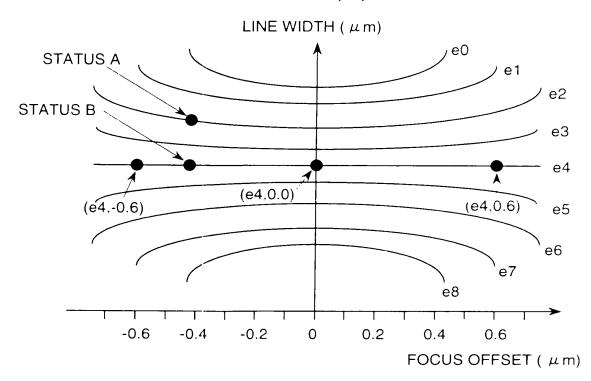


FIG. 20(b)

